

## Chemical Supply List and Location (Cleanroom-1)

November 10, 2005

### Cabinet #1

#### Top shelves, SU8 resist and Soft-lithography materials

SU-8 2002, 2010, 2015, 2025, 2050, 2100 photoresist

SU-8 50 photoresist

PDMS

#### Bottom shelves

**User storage**

### Cabinet #2, Hydrofluoric acid and wastes

Buffered Oxide Etch (HF) 7:1

Hydrofluoric acid

Ammonium Fluoride

### Cabinet #3, Solvents

Acetone

Methanol

Isopropyl Alcohol

Ethylene Glycol

Propyleneglycolmethylethylacetate (PGMEA), Baker BTS-220

Methyl Isobutyl Ketone (MIBK)

MIBK/IPA (1:3) developer

Trichloroethylene (TCE)

### Cabinet #4, Photoresist, primer and stripper

Hexamethyldisilazane (HMDS), photoresist primer

Microposit 1805, 1813, 1818, 1822 photoresist

LOR 3A

Microposit photoresist stripper/remover 1165

### Cabinet #5, Developer

Microposit 351, 353, 452 developer

MF-CD-26, CD-30 developer

MF-319 developer

SU-8 developer

### Acid Wet Bench

Acetic acid, Nitric acid, Sulfuric acid, Phosphoric acid

Hydrobromic acid, Hydrochloric acid

Ammonium Hydroxide, Potassium Hydroxide

Cyantek CR-7 chrome etch

Gold etch